

Supplementary Information

Fabrication of multiple nanopores in a SiN_x membrane via controlled breakdown

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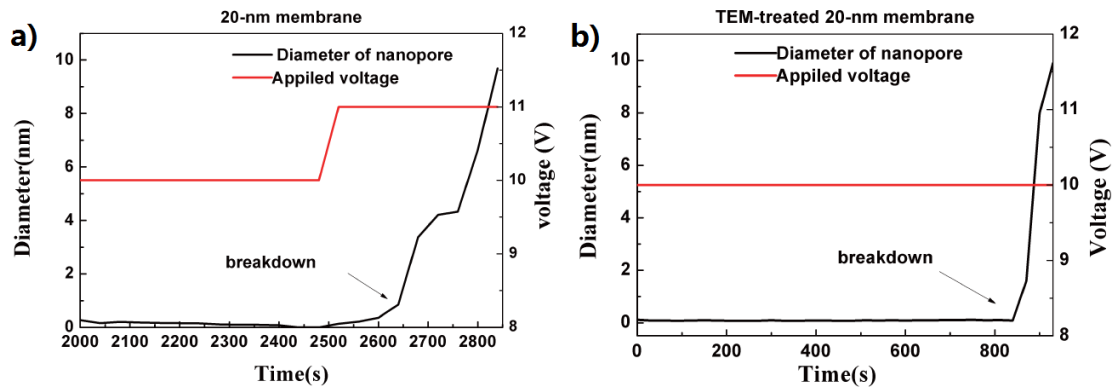


Figure S1. Time traces of voltage (red line) and derived nanopore diameter (black line) for (a) a 20-nm thick membrane and (b) TEM-treated membrane in dielectric breakdown process. For normal sample, no breakdown happens after applying 10 V for a long time (at least 2 hour). A nanopore formed after applying 11 V for 2650 seconds. While for a TEM-treated membrane, breakdown happens in 800s after applying 10 V, which is at least 4 times faster than normal sample.